

IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Justin K. Brask et al.	§	Art Unit:	2811
Serial No.:	10/626,336	§		
Filed:	July 24, 2003	§	Examiner:	Ori Nadav
For:	Forming a High Dielectric Constant Film Using Metallic Precursor	§	Atty Docket:	ITL.1022US P16709

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO PAPER NO. 0

Sir:

In response to the office action mailed September 24, 2004, please amend the above-referenced patent application as follows:

Date of Deposit: December 1, 2004
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.
Cynthia L. Hayden
Cynthia L. Hayden